CLAIMS:

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1. An apparatus for optical modulation, the apparatus comprising: an optical waveguide (10); and

a microwave waveguide (12), said microwave waveguide (12) having an electro-absorptive material (14) sized and placed such that, for an optical wave of interest guided in said optical waveguide (10), the electro-absorptive material (14) is located in an evanescent region (16) occupied by the optical wave's evanescent tail when the optical wave is being guided in said optical waveguide (10).

- 2. The apparatus recited in claim 1, wherein said optical waveguide (10) includes a substrate (18); an N-contact layer (26);
- an upper semiconducting cladding layer (20) disposed between said substrate (18) and said N-contact layer 20;
- a semiconducting core layer (22) disposed between said substrate (18) and said upper semiconducting cladding layer (20); and
 - a lower semiconducting cladding layer (24) disposed between said substrate (18) and said semiconducting core layer (22); and
- wherein N-contact layer (26) and an upper part of upper 20 semiconducting cladding layer (20) are etched down to form a ridge.
 - 3. The apparatus recited in claim 2, wherein said microwave waveguide (12) includes two N-contacts (28) disposed on said N-contact layer (26); said electro-absorptive material is disposed between and equidistant from said N-contacts (28) on said ridge of said upper

semiconducting cladding layer (20);

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- a P-contact layer (30) disposed on said EA material (14); and
- a P-contact (32) disposed on said P-contact layer (30).
- The apparatus recited in claim 3, wherein
 said N-contacts (28) are disposed at each outer edge of said ridge of said N-contact layer (26).
 - 5. The apparatus recited in claim 2, wherein said microwave waveguide (12) includes
- two N-contacts (28) disposed on said N-contact layer (26), each of said N-contacts (28) being disposed on either side of a main mode region (34) and said evanescent region (16) of said optical waveguide (10), wherein said N-contact layer (26) and said upper semiconducting cladding layer (20) have an etched-away area between each of said N-contacts (28) and said main mode region (34) and said evanescent region (16) of optical waveguide (10) to form a ridge;

said electro-absorptive material (14) disposed on said N-contact layer (26) on said ridge;

a P-contact layer (32) disposed on said electro-absorptive material (14) on either side of a top surface of said electro-absorptive material (14);

two insulators (35) disposed on said N-contact layer (20) in contact with side surfaces of said electro-absorptive material (14), wherein each of said insulators (35) is in contact with said P-contact layer (32), and wherein said P-contact layer (32) and said insulators (35) form an inverted V-shaped groove with a truncated tip at said top surface of said electro-absorptive material (14); and

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a P-contact (36) disposed in said V-shaped groove and extending at least to a top surface of each of said insulators (35).

- The apparatus recited in claim 5, wherein
 said N-contacts (26) are disposed at each edge of said etched away areas opposite said ridge formed by said etched-away areas.
 - 7. The apparatus recited in claim 5, wherein said apparatus has a microwave modulation voltage less than or equal to 0.3 V, has an optical saturation power of equal to or greater than 100mW,
- has an operating bandwidth equal to or greater than 40 GHz, has an effective thickness of EA material (14), $d_{i,eff}$, less than or equal to 0.1 μ m, and

has a microwave propagation loss per unit length, α_{rf} , less than or equal to 3 dB/mm;

- is capable of having a microwave wave guide in microwave waveguide (12) and an optical wave guided in optical waveguide (10) wherein a phase velocity of the microwave wave and a phase velocity of the optical wave are equal; and
- microwave waveguide (12) has an impedance capable of being 20 matched to a microwave driver, the microwave driver being capable of supply a microwave wave to be guided in said microwave waveguide (12).
 - 8. The apparatus recited in claim 1, wherein said electro-absorptive material (14) is a multiple quantum well material.

9. The apparatus recited in claim 1, wherein said electro-absorptive material (14) is a Franz-Keldysh material.

- The apparatus recited in claim 1, wherein
 said electro-absorptive material (14) is a group III-V compound material.
 - 11. The apparatus recited in claim 1, wherein said electro-absorptive material (14) is InGaAsP.
- The apparatus recited in claim 1, wherein
 said electro-absorptive material (14) is GaInAlAs.
 - 13. A method for optical modulation, said method comprising the steps of:

guiding an optical wave in an optical waveguide (10), said optical wave having an evanescent tail; and

- applying a modulation voltage to said evanescent tail.
 - 14. The method recited in claim 13, further comprising a step of: positioning an electro-absorptive material (14) in said evanescent tail of said optical wave; and

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- wherein said step of applying a modulation voltage to said evanescent tail is performed by applying said modulation voltage to said electro-absorptive material (14).
 - 15. The method recited in claim 13, wherein said modulation voltage is analog.

16. The method recited in claim 13, wherein said modulation voltage is digital.

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- 17. The method recited in claim 13, wherein said step of guiding said optical wave includes direct coupling a single mode fiber optical wave into said optical waveguide (10).
- 18. The method recited in claim 13, wherein an optical confinement factor of said electro-absorption material (14), Γ, between and 1% and 5% enables the optical modulation of an optical power equal to or greater than 100 mW.